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DATE: Tuesday, March 30, 2004

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Search Results – Record(s) 1 through 8 of 8 returned.

☐ 1. Document ID: WO 3098316 A2

Using default format because multiple data bases are involved.

L2: Entry 1 of 8

File: EPAB

Nov 27, 2003

PUB-NO: WO003098316A2

DOCUMENT-IDENTIFIER: WO 3098316 A2

TITLE: OPTICAL SYSTEM FOR HOMOGENIZING AN AT LEAST PARTIALLY COHERENT LIGHT FIELD

PUBN-DATE: November 27, 2003

INVENTOR-INFORMATION:

NAME	COUNTRY
STEINER, REINHARD	DE
RUDOLF, KLAUS	DE
BRUNNER, ROBERT	DE
BISCHOFF, JOERG	DE
TRAEGER, STEFAN	DE
KOWARSCHIK, RICHARD	DE
ZOELLNER, FRIEDRICH	DE
ECKARDT, PETER	DE
DARSCHT, MAXIM	DE

INT-CL (IPC): G02 B 26/00

EUR-CL (EPC): G02B027/48

Full	Title	Citation	Front	Review	Classification	Date	Reference	Abstract	Claims	KWIC	Draw D
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☐ 2. Document ID: WO 3065119 A2

L2: Entry 2 of 8

File: EPAB

Aug 7, 2003

PUB-NO: WO003065119A2

DOCUMENT-IDENTIFIER: WO 3065119 A2

TITLE: OVERLAY MEASUREMENTS USING PERIODIC GRATINGS

PUBN-DATE: August 7, 2003

INVENTOR-INFORMATION:

NAME	COUNTRY
BISCHOFF, JOERG	DE
NIU, XINHUI	US
JAKATDAR, NICKHIL	US

ASSIGNEE-INFORMATION:

NAME	COUNTRY
TIMBRE TECHNOLOGIES INC	US
BISCHOFF JOERG	DE
NIU XINHUI	US
JAKATDAR NICKHIL	US

APPL-NO: US00302201

APPL-DATE: January 24, 2003

PRIORITY-DATA: US06655502A (January 31, 2002)

INT-CL (IPC): G03 F 0/

ABSTRACT:

CHG DATE=20030912 STATUS=N>Overlay measurements for a semiconductor wafer are obtained by forming a periodic grating on the wafer having a first set of gratings and a second set of gratings. The first and second sets of gratings are formed on the wafer using a first mask and a second mask, respectively. The first and second sets of gratings are intended to be formed on the wafer with an intended asymmetrical alignment. A diffraction signal of the first and second sets of gratings is measured after the first and second sets of gratings are formed on the wafer. The misalignment between the first and second sets of gratings formed on the wafer is determined based on the measured diffraction signal.

Full	Title	Citation	Front	Review	Classification	Date	Reference	Claims	KMC	Draw D
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☐ 3. Document ID: WO 3029879 A1

L2: Entry 3 of 8

File: EPAB

Apr 10, 2003

PUB-NO: WO003029879A1

DOCUMENT-IDENTIFIER: WO 3029879 A1

TITLE: ARRAY FOR REDUCING THE COHERENCE OF A COHERENT RADIATION BEAM

PUBN-DATE: April 10, 2003

INVENTOR-INFORMATION:

NAME	COUNTRY
BURKHARDT, MATTHIAS	DE
MENCK, ALEXANDER	DE

BISCHOFF, JOERG	DE
STEINER, REINHARD	DE
ERDMANN, LARS	DE

ASSIGNEE-INFORMATION:

NAME	COUNTRY
CARL ZEISS MICROELECTRONIC SYS	DE
BURKHARDT MATTHIAS	DE
MENCK ALEXANDER	DE
BISCHOFF JOERG	DE
STEINER REINHARD	DE
ERDMANN LARS	DE

APPL-NO: EP00210475

APPL-DATE: September 18, 2002

PRIORITY-DATA: DE10148162A (September 28, 2001)

INT-CL (IPC): G02 B 27/48; G03 H 1/32; G02 B 5/02

EUR-CL (EPC): G02B005/02; G02B027/48

ABSTRACT:

CHG DATE=20031129 STATUS=O>The invention relates to an array for reducing the coherence of a coherent radiation beam (6), wherein a reflector (1) defining an inner space is provided with a diffusely reflecting inner surface (4), wherein said reflector (1) has an inlet hole (2) through which the radiation beam (6) can be injected into the inner space, in addition to an outlet hole (3) through which the rays of the radiation beam (6) can come out after at least one reflection on the inner surface (4).

Full	Title	Citation	Front	Review	Classification	Date	Reference			Claims	KWIC	Draw D
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☐ 4. Document ID: WO 3029875 A2

L2: Entry 4 of 8

File: EPAB

Apr 10, 2003

PUB-NO: WO003029875A2

DOCUMENT-IDENTIFIER: WO 3029875 A2

TITLE: LIGHTING SYSTEM

PUBN-DATE: April 10, 2003

INVENTOR-INFORMATION:

NAME	COUNTRY
ERDMANN, LARS	DE
STEINER, REINHARD	DE
BRUNNER, ROBERT	DE
BURKHARDT, MATTHIAS	DE
BISCHOFF, JOERG	DE

ASSIGNEE-INFORMATION:

NAME	COUNTRY
CARL ZEISS MICROELECTRONIC SYS	DE
ERDMANN LARS	DE
STEINER REINHARD	DE
BRUNNER ROBERT	DE
BURKHARDT MATTHIAS	DE
BISCHOFF JOERG	DE

APPL-NO: EP00210849

APPL-DATE: September 27, 2002

PRIORITY-DATA: DE10148167A (September 28, 2001)

INT-CL (IPC): G02 B 26/06

EUR-CL (EPC): G02B027/44; G02B027/48

ABSTRACT:

CHG DATE=20031220 STATUS=O>The invention relates to a lighting system comprising a coherence reducer (1) which is provided with a mirror (2). Said coherence reducer introduces different phase shifts into a supplied coherent beam cluster (10) by means of the mirror (2), according to the position in the beam cross-section, and produces an illumination beam cluster (11). The inventive system also comprises an illuminating optical arrangement which is arranged downstream from the coherence reducer (1) and is used to illuminate an object field. Said optical arrangement comprises a micro-optical arrangement (4; 19) having a plurality of optical elements (9; 20) which are arranged in the form of a raster, and an imaging optical arrangement (5) which is arranged downstream from the micro-optical arrangement (4; 19). According to the invention, the mirror comprises an element (2) having a surface which is divided into a plurality of parallel partial surfaces (8) which are staggered in the perpendicular direction in relation to their surface. The supplied beam cluster (10) is reflected off the partial surfaces (8) of the mirror in such a way that partial illumination beam clusters (11) project from the partial surfaces (8) of the mirror, together forming the illumination beam cluster having the different phase shifts.

Full	Title	Citation	Front	Review	Classification	Date	Reference			Claims	KWIC	Draw D
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☐ 5. Document ID: WO 3029793 A2

L2: Entry 5 of 8

File: EPAB

Apr 10, 2003

PUB-NO: WO003029793A2

DOCUMENT-IDENTIFIER: WO 3029793 A2

TITLE: MEASURING ARRAY

PUBN-DATE: April 10, 2003

INVENTOR-INFORMATION:

NAME	COUNTRY
DOBSCHAL, HANS-JUERGEN	DE
STEINER, REINHARD	DE

BISCHOFF, JOERG

DE

ASSIGNEE-INFORMATION:

NAME	COUNTRY
CARL ZEISS MICROELECTRONIC SYS	DE
DOBSCHAL HANS-JUERGEN	DE
STEINER REINHARD	DE
BISCHOFF JOERG	DE

APPL-NO: EP00210474

APPL-DATE: September 18, 2002

PRIORITY-DATA: DE10146944A (September 24, 2001)

INT-CL (IPC): G01 N 21/55; G01 N 21/21

EUR-CL (EPC): G01N021/21; G01N021/47, G01N021/55

ABSTRACT:

CHG DATE=20031213 STATUS=O>The invention relates to a measuring array having a radiation source (10), a deflecting device (5) arranged downstream thereof, which can be hit by a ray (2) coming out of the radiation source (1) and which deflects said ray successively in time in different directions. Said array also comprises a first and a second optical device (9, 10) and a detector (6), wherein the first optical device (9) deflects the rays coming from the deflecting device (5) in the form of measuring rays to a point (P) of a sample (11) that is to be arranged in a measuring position in such a way that the angle of incidence of the measuring ray on the sample (11) varies depending on the direction. The sample rays coming out of the sample (11) due to the interaction between the measuring rays and the sample are deflected by the second optical device (10) onto the detector (11). At least one of the two optical devices (9, 10) has a diffracting element (7) for deflection, said element diffracting the incident rays coming from different directions in such a way that the rays diffracted in a given diffraction order are focused on a point (P, D).

Full	Title	Citation	Front	Review	Classification	Date	Reference				Claims	KWIC	Draw D
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☐ 6. Document ID: WO 3029770 A1

L2: Entry 6 of 8

File: EPAB

Apr 10, 2003

PUB-NO: WO003029770A1

DOCUMENT-IDENTIFIER: WO 3029770 A1

TITLE: SCATTEROMETRIC MEASURING ARRAY AND MEASURING METHOD

PUBN-DATE: April 10, 2003

INVENTOR-INFORMATION:

NAME	COUNTRY
DOBSCHAL, HANS-JUERGEN	DE
MASCHKE, GUNTER	DE
BISCHOFF, JOERG	DE

ASSIGNEE-INFORMATION:

NAME	COUNTRY
CARL ZEISS MICROELECTRONIC SYS	DE
DOBSCHAL HANS-JUERGEN	DE
MASCHKE GUNTER	DE
BISCHOFF JOERG	DE

APPL-NO: EP00210476

APPL-DATE: September 18, 2002

PRIORITY-DATA: DE10146945A (September 24, 2001)

INT-CL (IPC): G01 J 4/00; G01 N 21/21

EUR-CL (EPC): G01N021/47; G01J003/28, G01J004/00 , G01N021/21

ABSTRACT:

The invention relates to a measuring array having an optical device into which a radiation beam (10) departing and diverging from a sample is injected for measurement and a detector (13) arranged downstream of said optical device, said detector having a plurality of detector pixels which are arranged on a plane and can be evaluated separately from one another, wherein the optical device (11) spectrally splits the diverging radiation beam (10) in a first direction crosswise to the direction of propagation of the radiation beam (10) and directs it towards the detector (13). The optical device parallelizes the radiation beam before it strikes the detector (13) in a second direction crosswise to the direction of propagation in such a manner that adjacent rays in the second direction of the radiation beam striking the detector (13) are parallel relative to one another.

Full	Title	Citation	Front	Review	Classification	Date	Reference			Claims	KWIC	Draw. De
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☐ 7. Document ID: DE 19925831 A1

L2: Entry 7 of 8

File: EPAB

Dec 14, 2000

PUB-NO: DE019925831A1

DOCUMENT-IDENTIFIER: DE 19925831 A1

TITLE: Process for measuring the positioning errors of structured patterns used in semiconductor production comprises forming test grating structures, and measuring the light bent at the structures

PUBN-DATE: December 14, 2000

INVENTOR-INFORMATION:

NAME	COUNTRY
BAUER, JOACHIM	DE
BISCHOFF, JOERG	DE

ASSIGNEE-INFORMATION:

NAME	COUNTRY
INST HALBLEITERPHYSIK GMBH	DE

APPL-NO: DE19925831

APPL-DATE: June 7, 1999

PRIORITY-DATA: DE19925831A (June 7, 1999)

US-CL-CURRENT: 257/E23.179INT-CL (IPC): G03 F 9/00; H01 L 23/544; G01 J 1/22

EUR-CL (EPC): H01L023/544; G03F007/20

ABSTRACT:

CHG DATE=20010601 STATUS=O>Positioning errors of structured patterns are measured by forming test grating structures (4, 7) in at least one plane; measuring light bent at the structures; determining connection between bent light and positioning of both test lattice structures to each other by calibrating and simulating; and determining positioning errors using intensity measurement of bent light of bending level(s). Preferred Process: The test grating structure is produced by etching a metal layer, an insulating layer or a semiconductor.

Full	Title	Citation	Front	Review	Classification	Date	Reference	Abstract	Claims	KWC	Drawings
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☐ 8. Document ID: DE 19827183 A1

L2: Entry 8 of 8

File: EPAB

Dec 23, 1999

PUB-NO: DE019827183A1

DOCUMENT-IDENTIFIER: DE 19827183 A1

TITLE: Method of optically preprocessing scattered light data

PUBN-DATE: December 23, 1999

INVENTOR-INFORMATION:

NAME	COUNTRY
BISCHOFF, JOERG	DE
BAUMGARD, JOERG	DE
TRUCKENBRODT, HORST	DE

ASSIGNEE-INFORMATION:

NAME	COUNTRY
TECH UNI ILMENAU ABTEILUNG FOR	DE

APPL-NO: DE19827183

APPL-DATE: June 18, 1998

PRIORITY-DATA: DE19827183A (June 18, 1998)

INT-CL (IPC): G06 T 5/10; G01 N 21/47; G06 K 9/66

EUR-CL (EPC): G01N021/47; G06N003/067

ABSTRACT:

CHG DATE=20001128 STATUS=O>The scattered light indicatrix is spatially evaluated by special filters and integrated using a lens. The filters are Gray level filters characterized by a specific spatial filter function. Alternatively they may be

spatial light modulators (4) whose filter functions can be adapted to the measurement output by device circuitry. An Independent claim is included for device to preprocess and analyze data using optical/electronic neural network.

Full	Title	Citation	Front	Review	Classification	Date	Reference	Abstract	Claims	KMC	Draw D
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(BISCHOFF-JOERG.IN.).USPT,EPAB.	8

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